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(54) Title: LITHOGRAPHY METHODS, AND ELEMENTS AND DEVICES OBTAINABLE BY THE METHODS

(57) Abstract: The present disclosure relates to lithography methods comprising using a novel organometallic compound, a polymer obtained by subjecting one or more of the compounds to polymerization conditions, a composition comprising the organometallic compound and/or the polymer, and developing a formed exposed resist film with one or more developers, thereby forming a patterned resist film. The present disclosure also provides an optical element, optically active device or optical or semiconductor device obtainable by a method as defined in the present disclosure.

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